K-238A

<u>PATENT</u>

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

h re Application of

Hun Gun PARK and Seok Cheon HA

Serial No.: 09/721,709

Group Art Unit: 2879

Confirm. No.: 4055

Examiner: Karabi Guharav

Filed:

November 27, 2000

For:

PLASMA DISPLAY PANEL

REPLY TO RESTRICTION REQUIREMENT

Assistant Commissioner for Patents Washington, D. C. 20231

Sir:

In reply to the Office Action of September 26, 2002 wherein restriction has been required, Applicants hereby elect Group II (claims 14-22) with traverse, for prosecution in the above-identified application.

It is respectfully submitted that Group III is generic to both Groups I and II. Claim 29 of Group III includes an exhaust path formed between first and second dielectric layers. Claim 8 of Group I includes a plurality of projections, which are formed to create an exhaust path between first and second dielectric layers and claim 14 of Group II includes a groove to create an exhaust path between first and second dielectric layers. Therefore, as an exhaust path is formed in each of claims 8, 14, and 29, Applicant respectfully submits that Group III is generic to both Groups I and II.

Additionally, Applicant respectfully submits that the subject matter of each of the designated inventions is sufficiently related that a thorough search for the subject matter of each of the designated inventions would encompass a search for the subject matter of the remaining designated inventions. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. See MPEP §803 in which it states that "if the search and examination of an entire application can be made without serious burden, the Examiner must examine it on the merits, even though it includes claims to distinct or independent inventions." It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicant and duplicative examination by the U.S. Patent and Trademark Office.

Therefore, Applicant respectfully requests that Group III be found generic and prosecuted in conjunction with Group II as elected. Applicant further respectfully submits that if Group III be found allowable, then Groups I and II also be found allowable. Finally, Applicant respectfully submits that Groups I and III are sufficiently related to Group II and therefore should also be examined.

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 16-0607 and please credit any excess fees to such deposit account.

Respectfully submitted,

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